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| Docket Number (Optional) | Application Number |
| TWI-10820 | 09/629,407 |
| Applicant(s) | |
| Allan Rosenewaig et al. | |

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| Filing Date | Group Art Unit |
| August 1, 2000 | 2876 |

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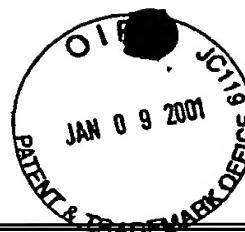
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PATENT

Sheet 1 of 1

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| INFORMATION DISCLOSURE CITATION (Use several sheets if necessary) | | | | Applicant(s) Allan Rosencwaig et al. | | | |
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